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(54) **SEMICONDUCTOR MEMORY DEVICE**

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(52) **U.S. Cl.**

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(57) **ABSTRACT**

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Related U.S. Application Data

(60) Provisional application No. 62/393,150, filed on Sep.
12, 2016.

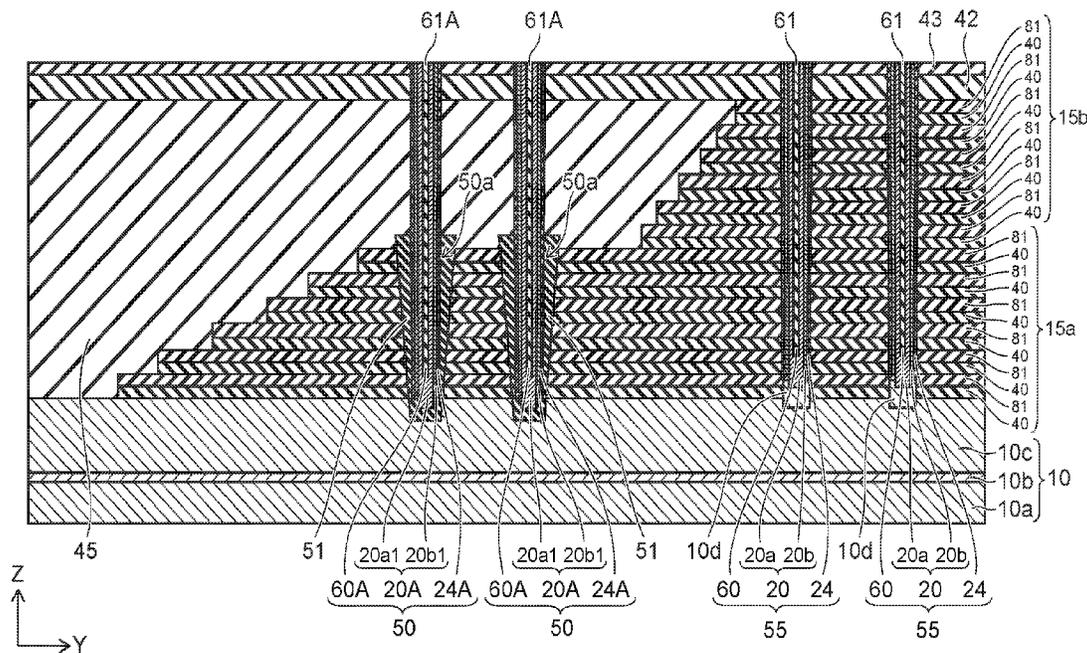
Publication Classification

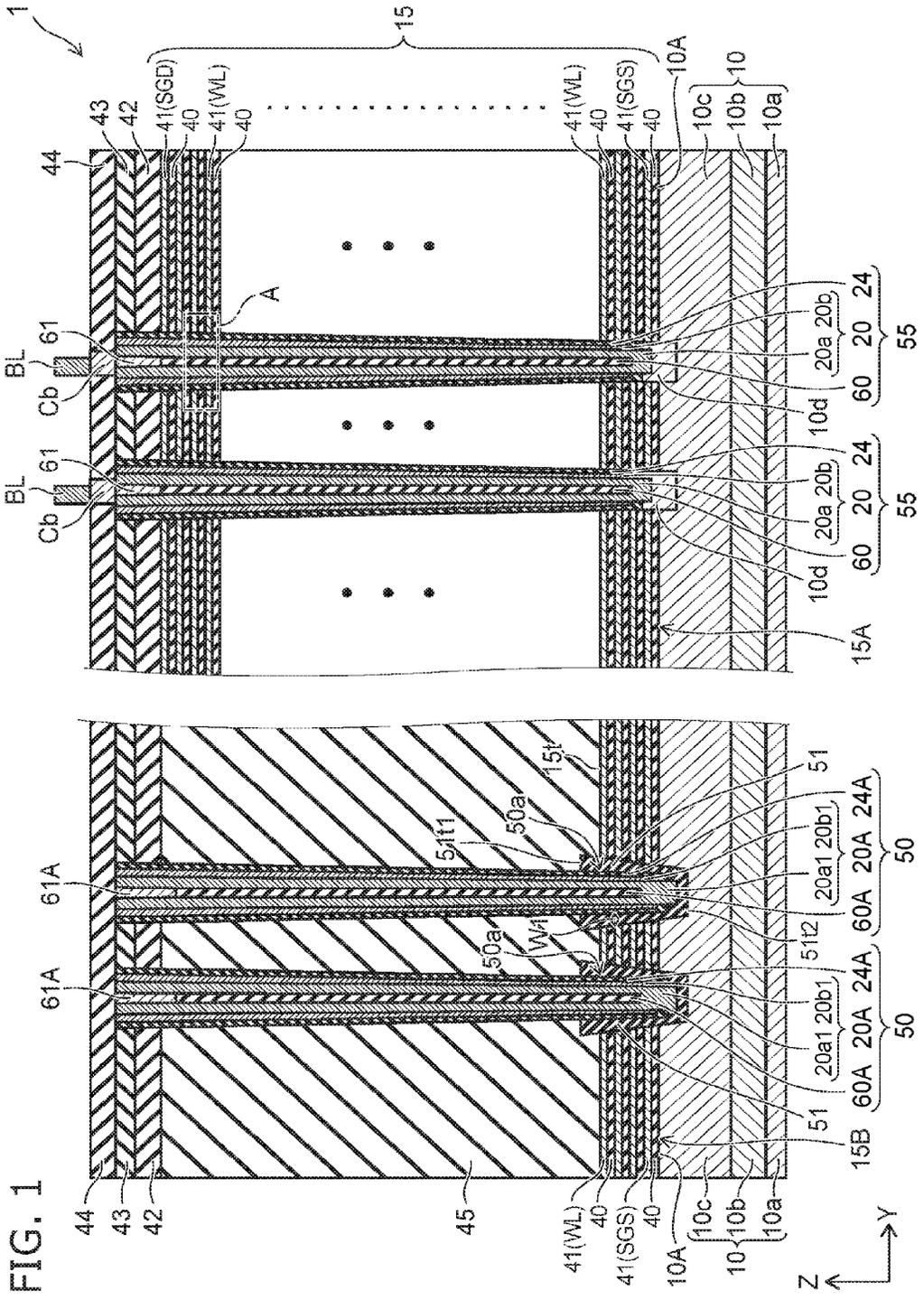
(51) **Int. Cl.**

H01L 27/11582 (2006.01)

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According to one embodiment, a semiconductor memory device includes a substrate, a stacked body, a columnar member, and an insulating film. The stacked body is provided on the substrate, and includes a plurality of electrode layers separately stacked each other. The columnar member is provided in the stacked body, and includes a first semiconductor portion extending in a stacked direction of the plurality of electrode layers. The insulating film covers a bottom portion of the columnar member.





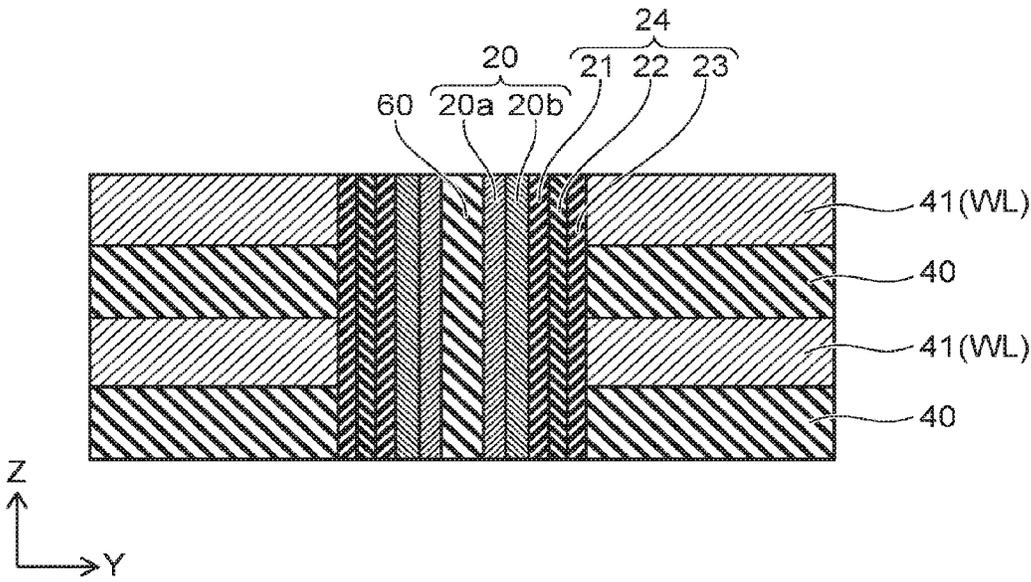


FIG. 2

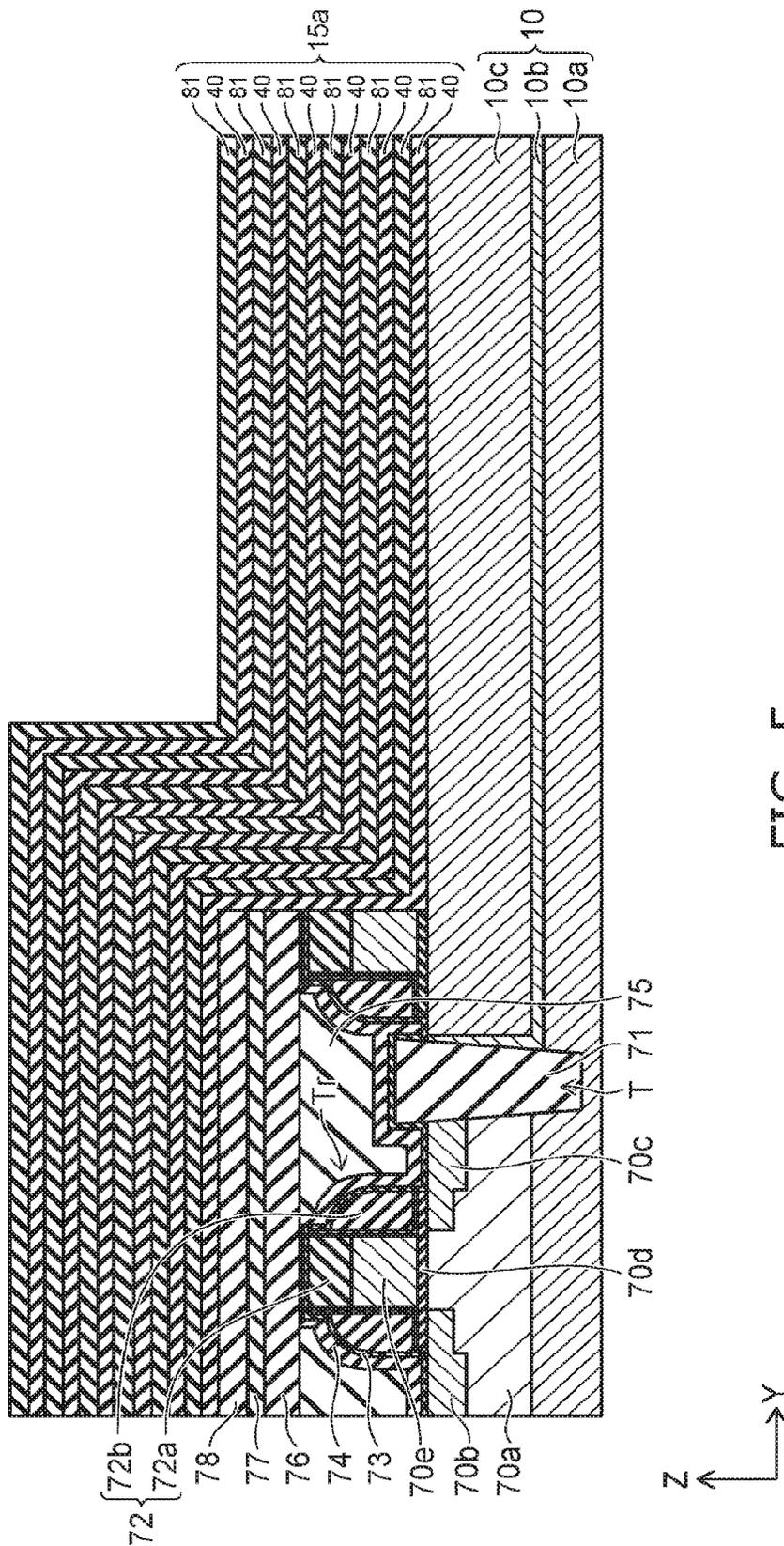


FIG. 5

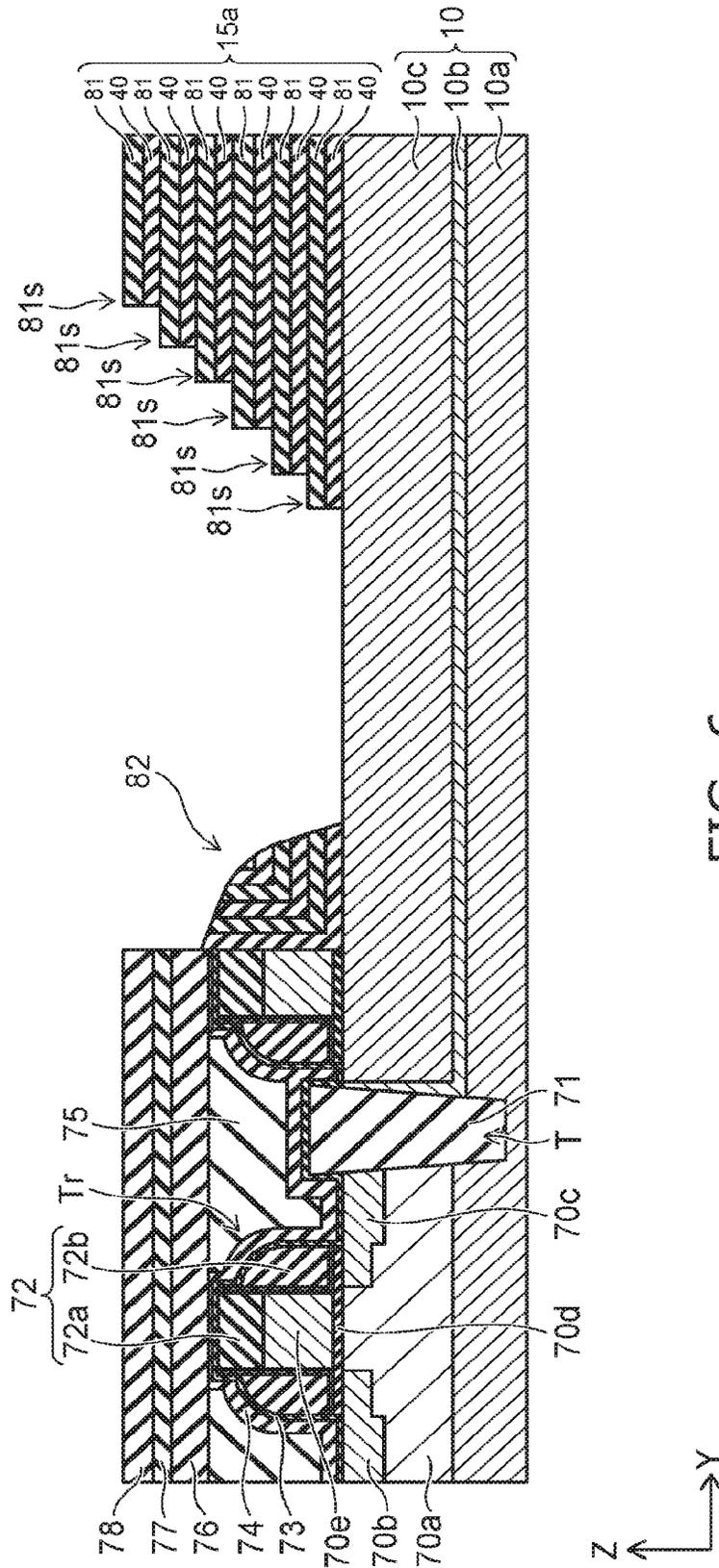


FIG. 6

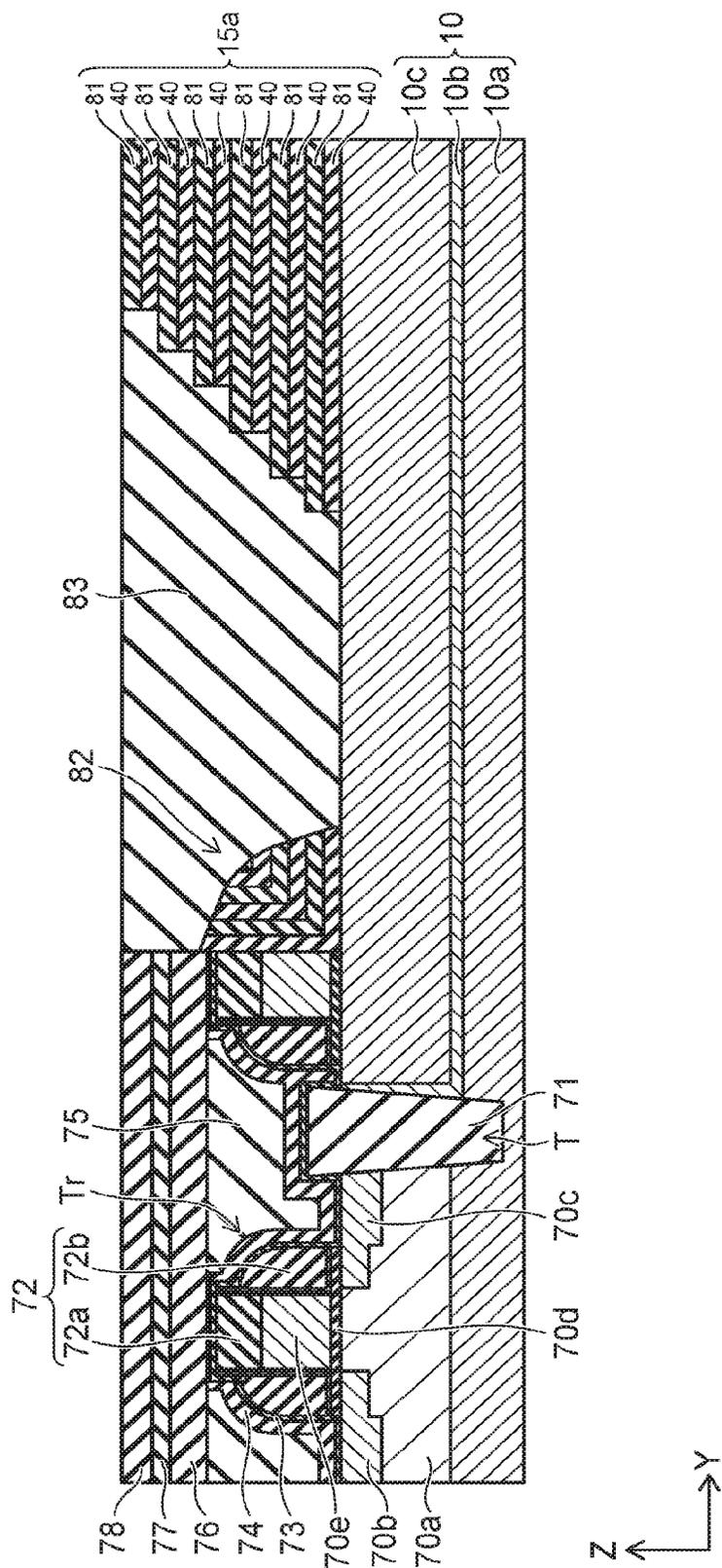


FIG. 7

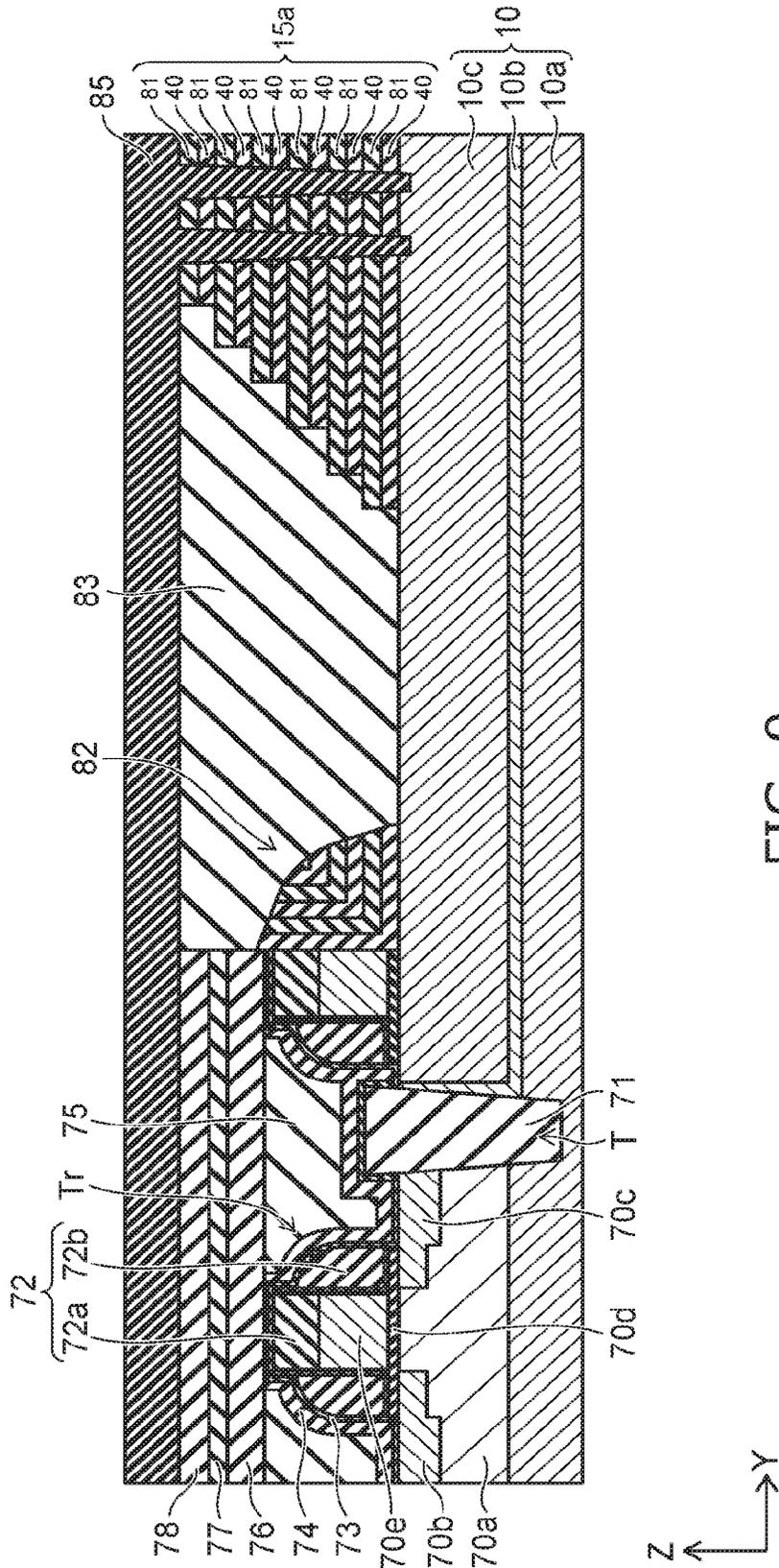


FIG. 9

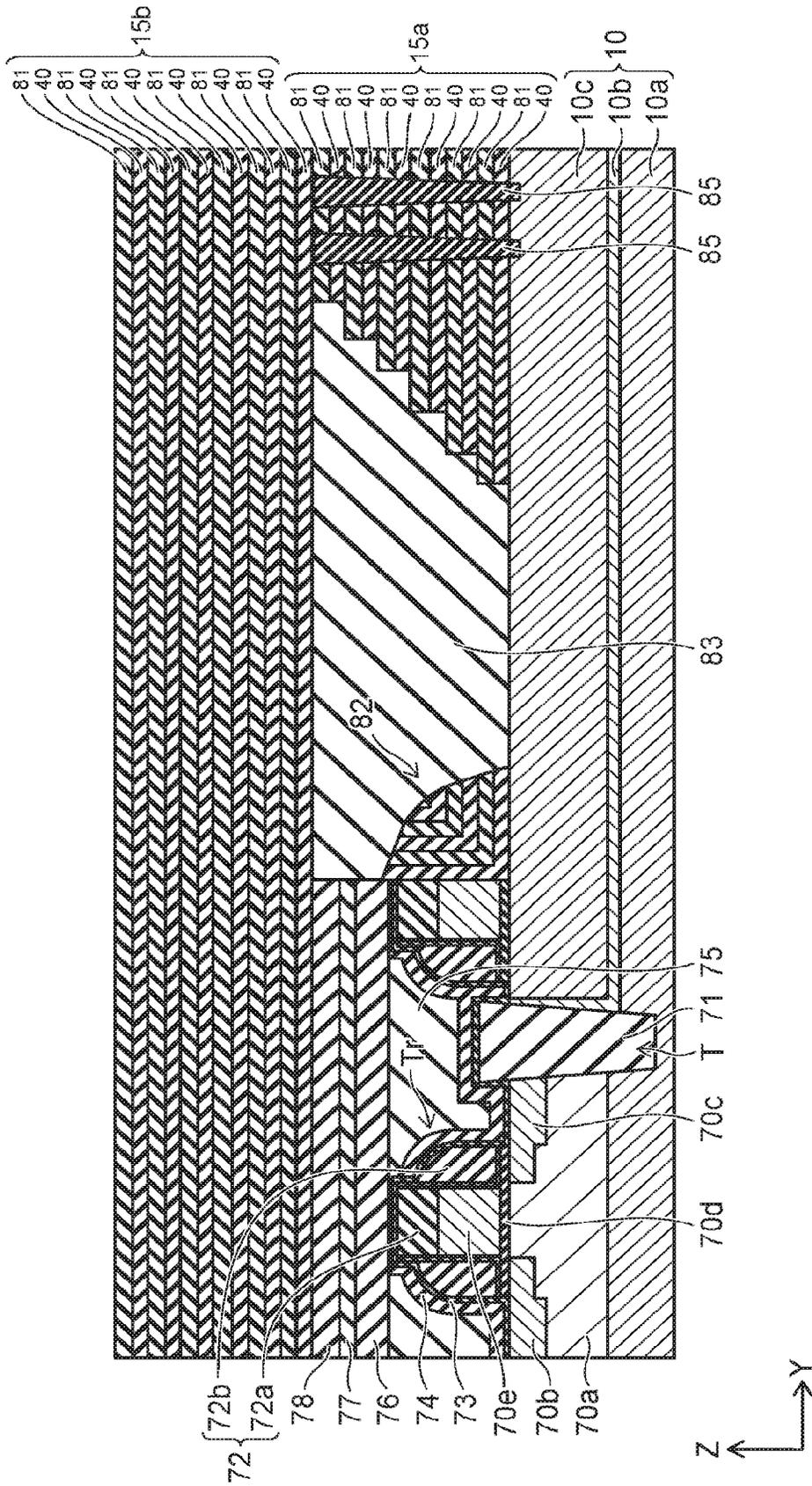


FIG. 11

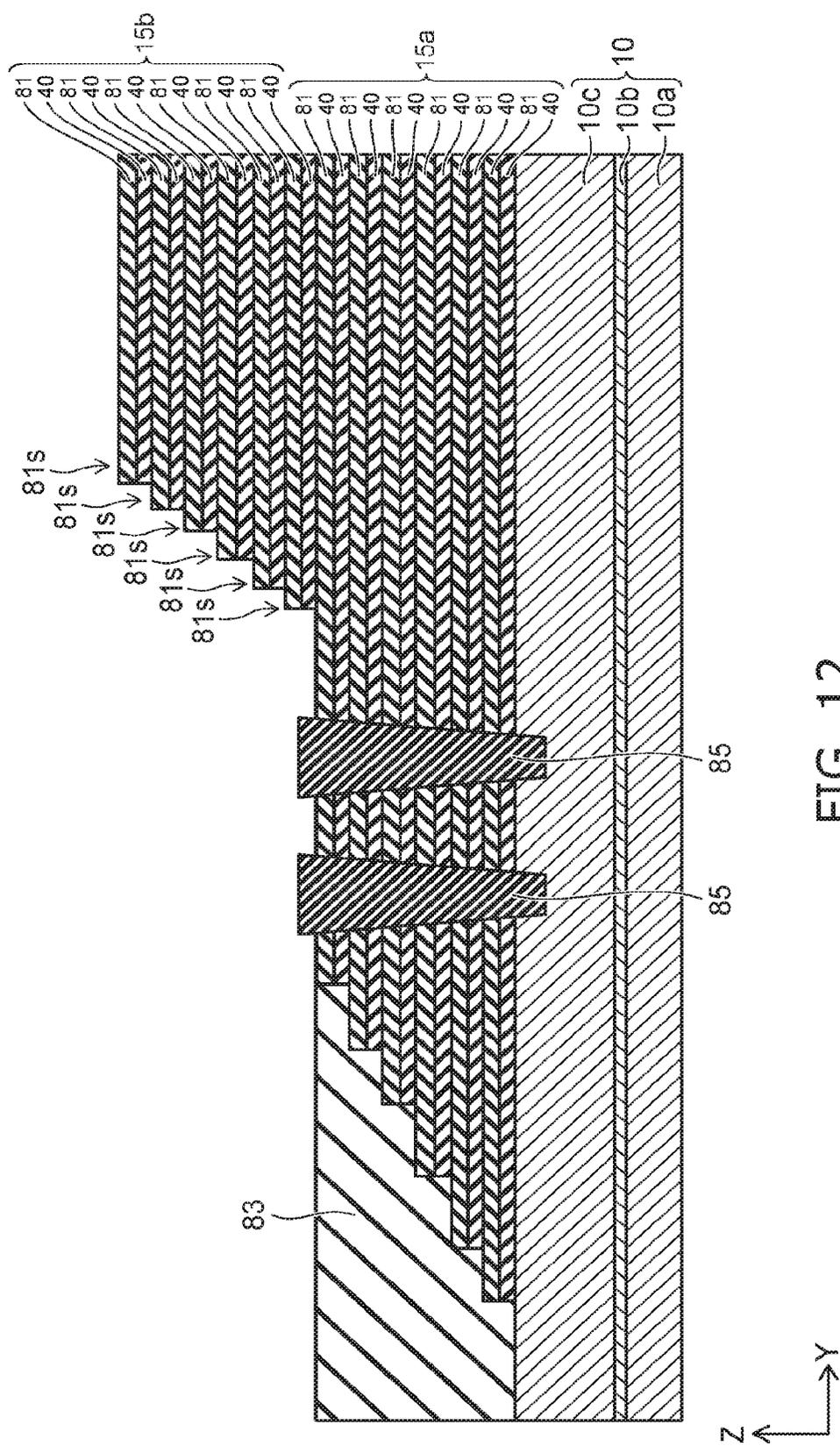


FIG. 12

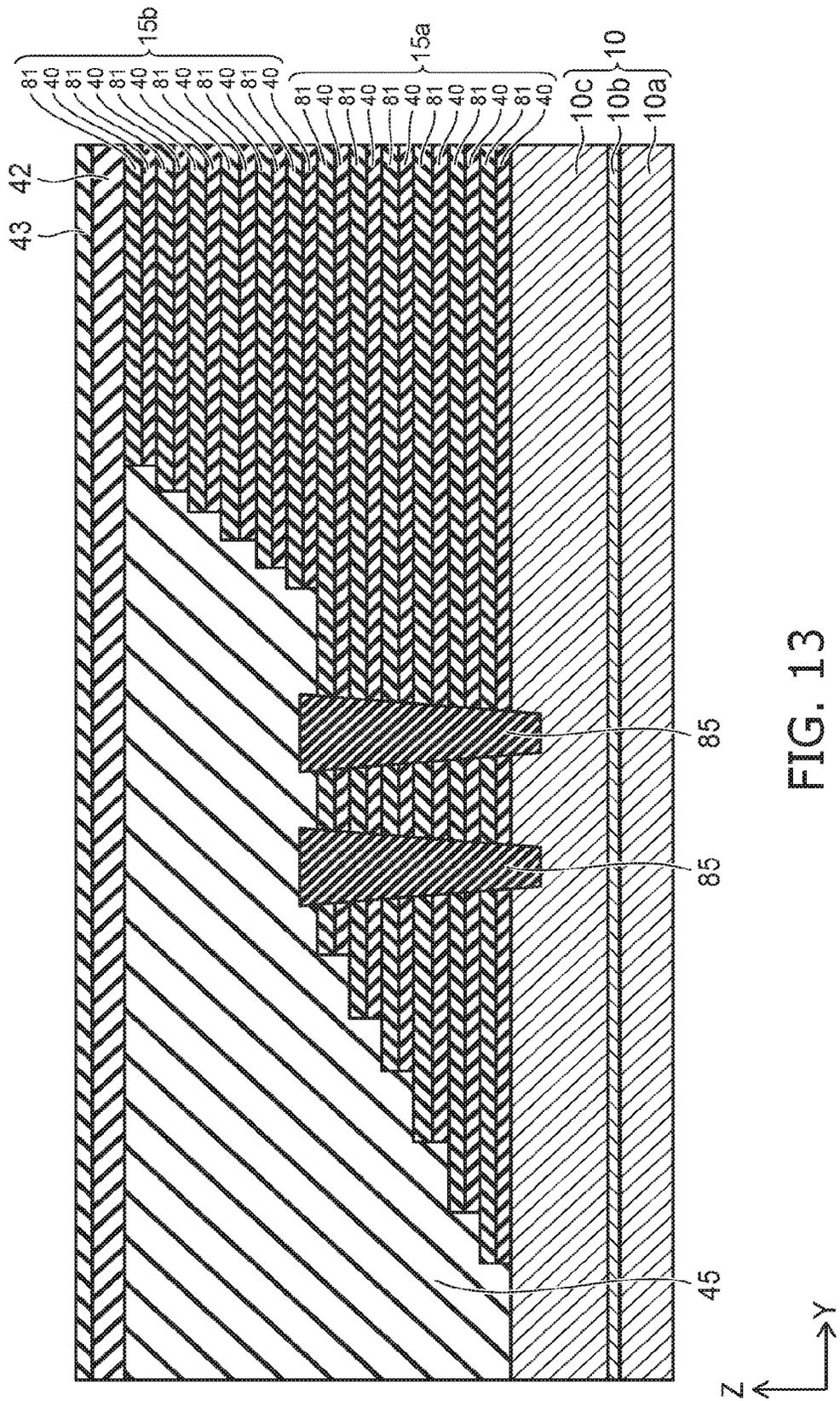


FIG. 13

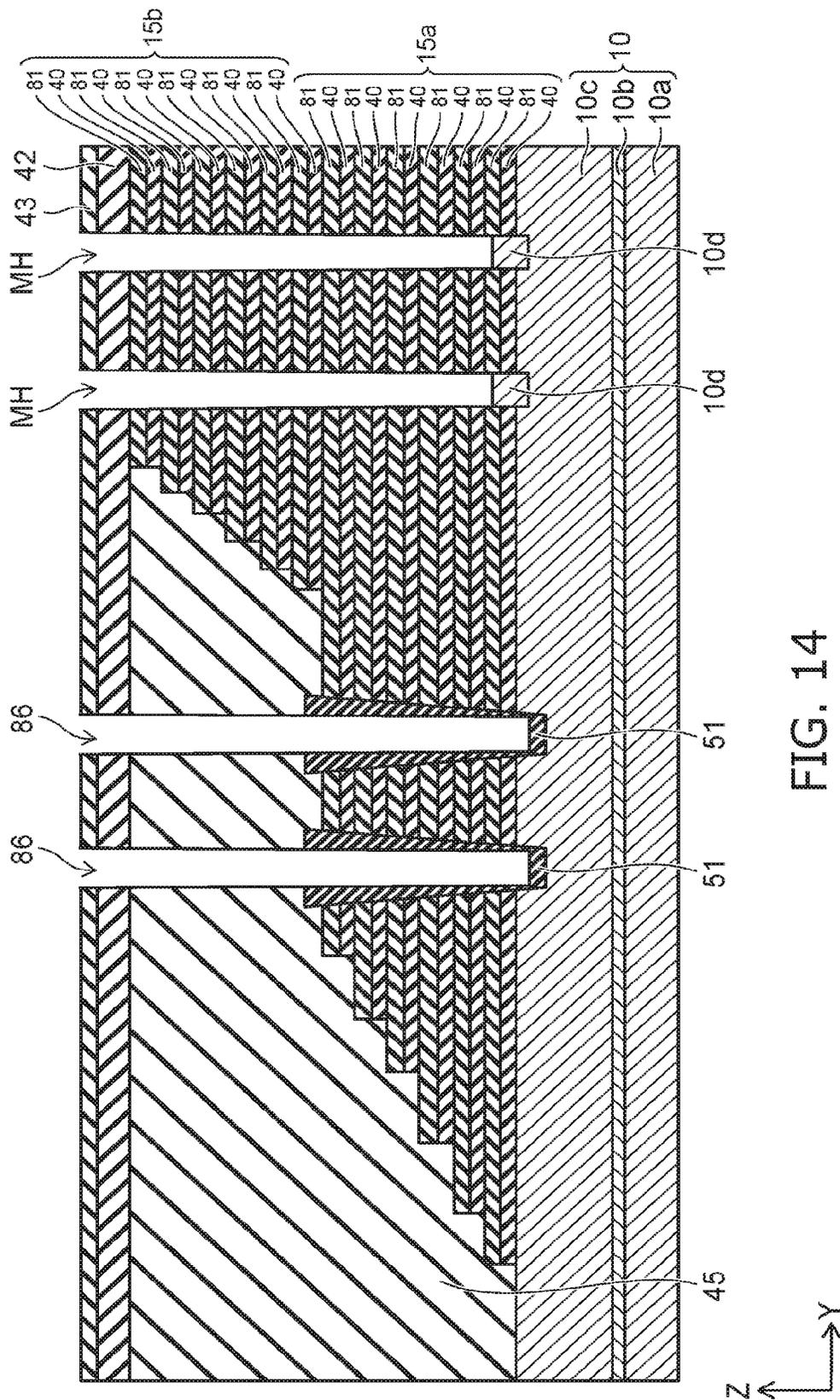


FIG. 14

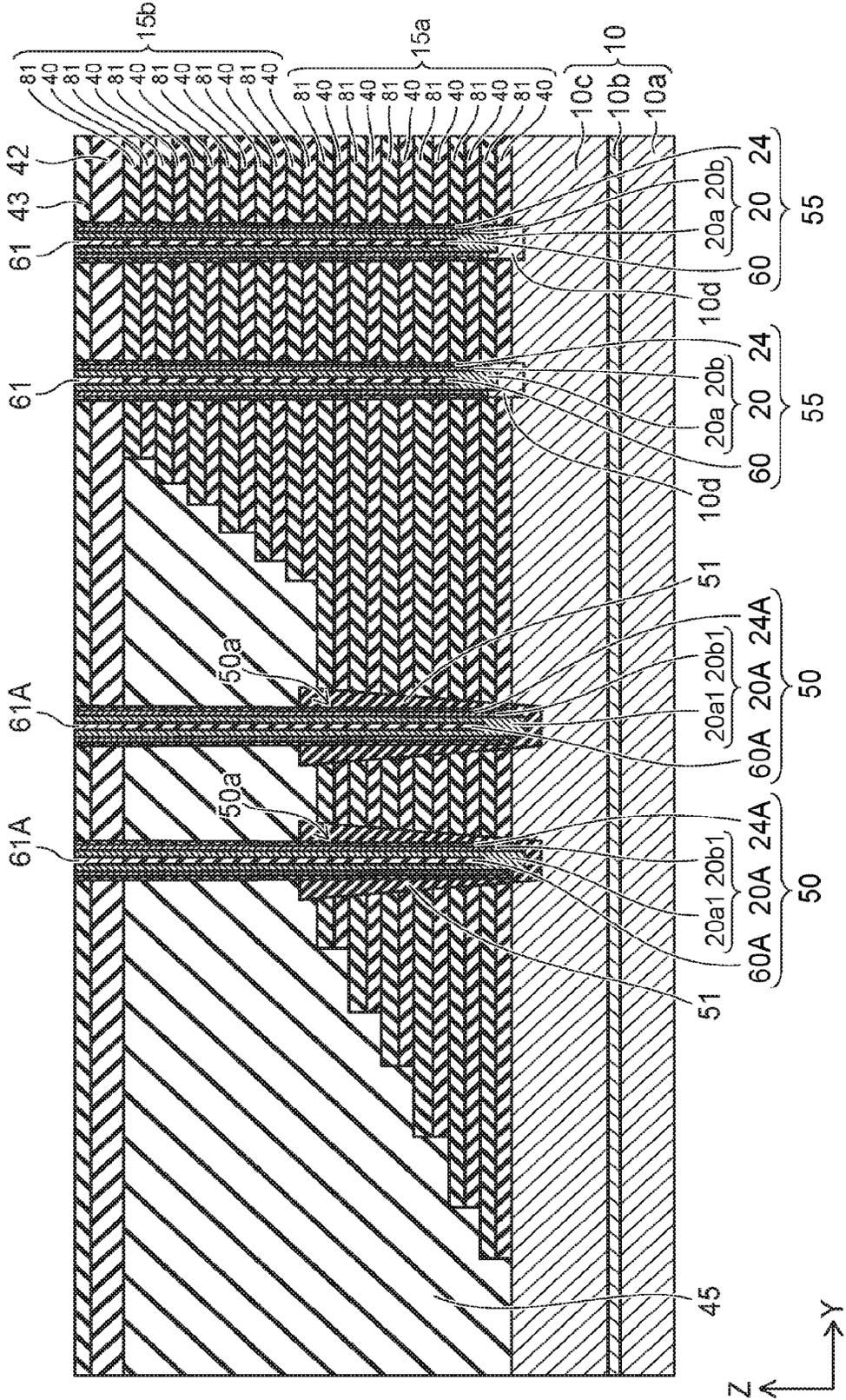


FIG. 15

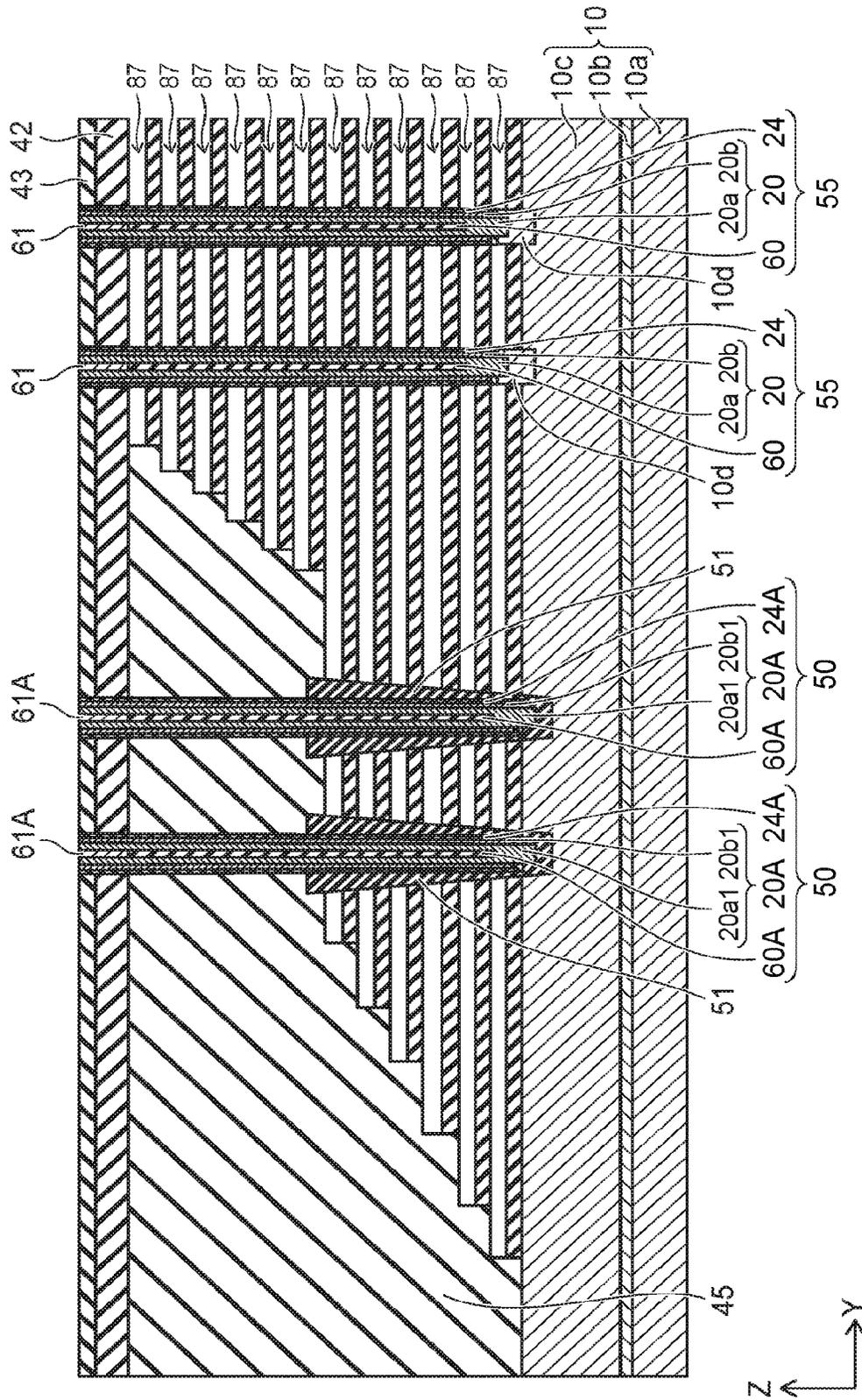


FIG. 16

SEMICONDUCTOR MEMORY DEVICE

CROSS-REFERENCE TO RELATED APPLICATIONS

[0001] This application is based upon and claims the benefit of priority from U.S. Provisional Patent Application 62/393,150 filed on Sep. 12, 2016; the entire contents of which are incorporated herein by reference.

FIELD

[0002] Embodiments described herein relate generally to a semiconductor memory device.

BACKGROUND

[0003] A three-dimensional structure memory device is proposed in which memory holes are formed in a stacked body of a plurality of electrode layers, and in which a charge storage film and a channel extending in the stacked direction of the stacked body are provided in the memory holes. The electrode layers are formed by filling metal or other material in cavities formed by removing a part of the stacked body. A columnar support is provided in the stacked body to reduce deformation of the electrode layers caused by warping of the stacked body due to the cavities. Shorting via the support is of concern.

BRIEF DESCRIPTION OF THE DRAWINGS

[0004] FIG. 1 is a cross sectional view showing a semiconductor memory device according to an embodiment;
 [0005] FIG. 2 is an enlarged view of region A of FIG. 1;
 [0006] FIG. 3 is a plan view showing the semiconductor memory device according to the embodiment; and
 [0007] FIG. 4 to FIG. 17 are cross sectional views showing a method for manufacturing the semiconductor memory device according to the embodiment.

DETAILED DESCRIPTION

[0008] According to one embodiment, a semiconductor memory device includes a substrate, a stacked body, a columnar member, and an insulating film. The stacked body is provided on the substrate, and includes a plurality of electrode layers separately stacked each other. The columnar member is provided in the stacked body, and includes a first semiconductor portion extending in a stacked direction of the plurality of electrode layers. The insulating film covers a bottom portion of the columnar member.

[0009] Hereinafter, embodiments will be described with reference to the drawings. Incidentally, in the respective drawings, the same elements are denoted by the same reference numerals.

Embodiment

[0010] FIG. 1 is a cross sectional view showing a semiconductor memory device according to an embodiment.

[0011] FIG. 2 is an enlarged view of region A of FIG. 1.

[0012] As shown in FIG. 1, a semiconductor memory device 1 includes a stacked body 15, columnar members 55, and columnar members 50.

[0013] The stacked body 15 is provided on a semiconductor substrate 10. The semiconductor substrate 10 contains, for example, silicon (Si). The semiconductor substrate 10 includes a P-type substrate 10a, an N-well region 10b, and

a P-well region 10c. The N-well region 10b is formed on the P-type substrate 10a. The P-well region 10c is formed on the N-well region 10b.

[0014] In the specification, two directions that are parallel to the upper surface 10A of the semiconductor substrate 10, and that are orthogonal to each other will be referred to as X-direction and Y-direction. A direction orthogonal to both X-direction and Y-direction is Z-direction.

[0015] The stacked body 15 has a plurality of electrode layers 41, and a plurality of insulating layers 40. The lowermost electrode layer 41 in the plurality of electrode layers 41 is a source-side select gate SGS, and is provided on the semiconductor substrate 10 via the insulating layer 40. The uppermost electrode layer 41 in the plurality of electrode layers 41 is a drain-side select gate SGD. The electrode layers 41 provided between the lowermost electrode layer 41 (source-side select gate SGS) and the uppermost electrode layer 41 (drain-side select gate SGD) in the plurality of electrode layers 41 are word lines WL. The electrode layers 41 contain, for example, metals such as tungsten (W). The electrode layers 41 may be stacked in any number.

[0016] The insulating layers 40 are provided between the electrode layers 41. The insulating layers 40 contain, for example, silicon oxide (SiO).

[0017] The stacked body 15 has a central portion 15A, and an end portion 15B. The columnar members 55 are provided in the central portion 15A. The columnar members 50 are provided in the end portion 15B. The end portion 15B has a stepped shape with a step provided for each electrode layer 41 (see FIG. 3). The central portion 15A and the end portion 15B are disposed along Y-direction.

[0018] Insulating layers 42, 43, and 44 are provided on the central portion 15A of the stacked body 15, in order. The insulating layers 42, 43, and 44 contain, for example, silicon oxide.

[0019] An insulating layer 45 is provided on the end portion 15B of the stacked body 15, covering the end portion 15B. The insulating layer 45 contains, for example, silicon oxide. The insulating layers 42, 43, and 44 are provided on the insulating layer 45, in order.

[0020] The columnar members 55 are provided in the central portion 15A of the stacked body 15. The columnar members 55 extend in Z-direction in the central portion 15A. The columnar members 55 have a form of, for example, a circular cylinder, or an elliptical cylinder.

[0021] The columnar members 55 have a core portion 60, a channel 20, and a memory film 24.

[0022] The core portion 60 contains, for example, silicon oxide. The core portion 60 has, for example, a circular cylinder shape.

[0023] A plug portion 61 is provided at the upper end of the core portion 60. The plug portion 61 is in the insulating layers 42 and 43, and surrounded by the channel 20. The plug portion contains, for example, a polysilicon crystallized from amorphous silicon.

[0024] The channel 20 is provided around the core portion 60. The channel 20 is a semiconductor portion, and includes a body 20a, and a cover layer 20b. The body 20a has a shape of, for example, a bottomed cylinder. The cover layer 20b is provided around the body 20a. The cover layer 20b has, for example, a cylindrical shape.

[0025] The body **20a** and the cover layer **20b** contain a polysilicon crystallized from silicon, for example, amorphous silicon.

[0026] The lower end of the channel **20** is in contact with the semiconductor substrate **10**. For example, as shown in FIG. 1, the body **20a** of the channel **20** is in contact with a connecting member **10d** formed in the semiconductor substrate **10**. The connecting member **10d** is a member formed inside the semiconductor substrate **10**, and into the central portion **15A** of the stacked body **15**, and is formed by, for example, epitaxial growth of silicon. For example, the upper portion of the connecting member **10d** is located in the stacked body **15**, whereas the lower portion is in the P-well region **10c** of the semiconductor substrate **10**.

[0027] The memory film **24** is provided around the channel **20**. As shown in FIG. 2, the memory film **24** includes a tunnel insulating film **21**, a charge storage film **22**, and a block insulating film **23**. The tunnel insulating film **21** is provided around the channel **20**. The tunnel insulating film **21** contains, for example, silicon oxide. The tunnel insulating film **21** has, for example, a cylindrical shape.

[0028] The charge storage film **22** is provided around the tunnel insulating film **21**. The charge storage film **22** contains, for example, silicon nitride (SiN). The charge storage film **22** has, for example, a cylindrical shape. A memory cell including the charge storage film **22** is formed at the intersections of the channels **20** and the word lines WL.

[0029] The tunnel insulating film **21** is a potential barrier between the charge storage film **22** and the channel **20**. The tunnel insulating film **21** is where the charge tunnels through when moving from the channel **20** to the charge storage film **22** (write operation), and from the charge storage film **22** to the channel **20** (erase operation).

[0030] The charge storage film **22** has trapping sites for trapping charge. The threshold value of the memory cell varies with the presence or absence of a trapped charge at the trapping sites, and the amount of trapped charge. The memory cell retains information in this fashion.

[0031] The block insulating film **23** is provided around the charge storage film **22**. The block insulating film **23** contains, for example, silicon oxide. The block insulating film **23** protects, for example, the charge storage film **22** from etching when forming the electrode layers **41**. The block insulating film **23** may be a laminate of a silicon oxide film, and an aluminum oxide film.

[0032] Above the columnar members **55** is provided a plurality of bit lines BL that extends in X-direction. The bit lines BL are connected to the columnar members **55** via the contact portions Cb. The contact portions Cb are disposed in the insulating layer **44**, with the upper end connected to the bit lines BL, and the lower end connected to the plug portions **61**. The contact portions Cb are formed of a conductor such as a metal.

[0033] The columnar members **50** are provided in the end portion **15B** of the stacked body **15**. The columnar members **50** extend in Z-direction in the end portion **15B**. The columnar members **50** include at least some of the elements of the columnar members **55**.

[0034] In the case where the columnar members **50** have all of the elements of the columnar members **55**, the columnar members **50** include a core portion **60A**, a channel **20A**, and a memory film **24A**, as shown in FIG. 1. The core portion **60A** of the columnar members **50** contains the same material, for example, silicon oxide, contained in the core

portion **60** of the columnar members **55**. The channel **20A** of the columnar members **50** is a semiconductor portion, and has a body **20a1**, and a cover layer **20b1**. The channel **20A** contains the same material, for example, polysilicon, contained in the channel **20** of the columnar members **55**. As with the case of the memory film **24** of the columnar members **55**, the memory film **24A** of the columnar members **50** is formed as a laminated film, and contains the same material contained in the memory film **24**.

[0035] A plug portion **61A** is provided at the upper end of the core portion **60A** of the columnar members **50**.

[0036] An insulating film **51** is provided in the end portion **15B** of the stacked body **15**. The insulating film **51** covers the bottom portion **50a** of the columnar members **50**. The bottom portion **50a** is a portion of the columnar members **50** located in the semiconductor substrate **10** and in the end portion **15B** of the stacked body **15**.

[0037] The insulating film **51** contains, for example, silicon oxide (SiO). The insulating film **51** has a shape of, for example, a bottomed cylinder.

[0038] The upper end **51/1** of the insulating film **51** is in contact with the insulating layer **45**, and is higher than, for example, the upper end **15t** of the stacked body **15**. The upper end **15t** of the stacked body **15** is at the same level as the step **41s** of the electrode layer **41** (see FIG. 3). The upper end **51/1** of the insulating film **51** may be at substantially the same level as the upper end **15t** of the stacked body **15**.

[0039] The lower end **51/2** of the insulating film **51** is in contact with the semiconductor substrate **10**. For example, the lower end **51/2** is in contact with the semiconductor substrate **10**, inside the P-well region **10c**.

[0040] For example, the insulating film **51** becomes thinner toward the lower layers of the stacked body **15**. For example, the thickness **W1** of the insulating film **51** between the stacked body **15** and the memory film **24A** becomes smaller toward the lower layers of the stacked body **15**. The thickness **W1** of the insulating film **51** may be substantially the same along Z-direction.

[0041] FIG. 3 is a plan view showing the semiconductor memory device according to the embodiment.

[0042] The bit lines BL are omitted in FIG. 3.

[0043] As shown in FIG. 3, the semiconductor memory device **1** has a memory cell region Rmc, a contact region Rc, and a skirt region Rs. The memory cell region Rmc, the contact region Rc, and the skirt region Rs are disposed along Y-direction.

[0044] The memory cell region Rmc includes the central portion **15A** of the stacked body **15**, and the columnar members **55** are disposed in the memory cell region Rmc. The columnar members **55** are disposed, for example, in a matrix on X-Y plane.

[0045] A plurality of slits ST is formed in the memory cell region Rmc and the contact region Rc. The slits ST are formed in the stacked body **15**. The slits ST extend in Z-direction and Y-direction in the stacked body **15**. The slits ST separate the stacked body **15** in X-direction. Each region separated by the slits ST is called "block". A selected columnar member **55** from each block is electrically connected to one of the bit lines BL.

[0046] An interconnect portion **18** is provided in the slits ST. The interconnect portion **18** extends in Z-direction and Y-direction. The interconnect portion **18** contains, for example, a metal such as tungsten. The upper end of the interconnect portion **18** is connected via a contact to a source

line (not shown) provided on the stacked body 15. The lower end of the interconnect portion 18 is in contact with the semiconductor substrate 10.

[0047] Inside the slits ST, an insulating film (not shown) is provided on side walls of the interconnect portion 18. The insulating film insulates the interconnect portion 18 from the electrode layers 41 of the stacked body 15.

[0048] The contact region Rc includes the end portion 15B of the stacked body 15, and the columnar members 50 are disposed in the contact region Rc. The end portion 15B has a stepped shape with a step provided for each electrode layer 41. The step 41s is formed for each electrode layer 41.

[0049] A contact 30 is provided on each step 41s. The contact 30 extends in Z-direction. The upper end of the contact 30 is connected to an upper-layer word line (not shown). The lower end of the contact 30 is connected to the electrode layer 41. Each electrode layer 41 is connected to a single upper-layer word line via the contact 30.

[0050] The columnar members 50 extend in Z-direction through the step 41s. In the example shown in FIG. 3, the stacked body 15 has a total of seven electrode layers 41, and steps 41s1 to 41s7 are formed at the end portion 15B of the stacked body 15. The step 41s1 is formed for the uppermost electrode layer 41 (drain-side select gate SGD), and the step 41s7 is formed for the lowermost electrode layer 41 (source-side select gate SGS). The columnar members 50 extend in Z-direction through the step 41s4.

[0051] As shown in FIG. 1, the columnar members 50 extend in Z-direction in the end portion 15B of the stacked body 15, and in the insulating layer 45. At the end portion 15B, the insulating film 51 covers the side and bottom surfaces of the columnar members 50.

[0052] A plurality of transistors Tr (see FIG. 4 to FIG. 11) is provided as switching elements in the skirt region Rs. The transistors Tr are disposed on the semiconductor substrate 10 according to a known method. The transistors Tr constitute a peripheral circuit, and, for example, a part of the transistors Tr is connected to the electrode layers 41 via the contact 30 and the upper-layer word line.

[0053] In the memory cell region Rmc, the memory cell including the charge storage film 22 is formed at the intersections of the channels 20 and the word lines WL. The plurality of memory cells is arranged in a three-dimensional matrix along X-, Y-, and Z-directions. The memory cells are adapted so that data are stored in each memory cell, using the word line WL as a gate electrode. In the contact region Rc and the skirt region Rs, the electrode layers 41 are connected to the peripheral circuit via, for example, the contacts 30 by being led out.

[0054] FIG. 4 to FIG. 17 are cross sectional views showing a method for manufacturing the semiconductor memory device according to the embodiment.

[0055] FIG. 4 to FIG. 11 are magnified Y-Z cross sectional views showing a manufacturing process of the contact region Rc and the skirt region Rs of the semiconductor memory device 1 shown in FIG. 3. FIG. 12 to FIG. 17 are magnified Y-Z cross sectional views showing a manufacturing process of the memory cell region Rmc and the contact region Rc of the semiconductor memory device 1 shown in FIG. 3.

[0056] The manufacturing process of the contact region Rc and the skirt region Rs is described first with reference to FIG. 4 to FIG. 11.

[0057] As shown in FIG. 4, an intermediate structure is formed by using a known method. In the intermediate structure shown in FIG. 4, a channel region 70a, a source region 70b, and a drain region 70c are provided on the P-type substrate 10a. The source region 70b and the drain region 70c are mutually distal to each other, and the channel region 70a is between the source region 70b and the drain region 70c.

[0058] A gate insulating film 70d is provided on the channel region 70a, and a gate electrode 70e is provided on the gate insulating film 70d. For example, the gate electrode 70e is a stacked body of a polysilicon-containing layer and a tungsten-containing layer.

[0059] The transistor Tr is configured from the channel region 70a, the source region 70b, the drain region 70c, the gate insulating film 70d, and the gate electrode 70e. The peripheral circuit is configured by disposing a plurality of transistors Tr.

[0060] In the intermediate structure, the N-well region 10b and the P-well region 10c are provided on the P-type substrate 10a, in order. An STI 71 is provided in a trench T extending in X-, Z-directions. The STI 71 divides the channel region 70a, the source region 70b, and the drain region 70c from the N-well region 10b and the P-well region 10c. The semiconductor substrate 10 including the substrate 10a, the N-well region 10b, and the P-well region 10c is configured as a result. A recessed portion 80 is formed on the P-well region 10c of the semiconductor substrate 10.

[0061] In the intermediate structure, insulating films 72a and 72b are provided on the upper surface and the side surface, respectively, of the gate electrode 70e. For example, the insulating film 72a contains silicon nitride, and the insulating film 72b contains silicon oxide. The insulating films 72a and 72b represent a protective film 72 for the transistor Tr.

[0062] Insulating films 73 and 74, and an insulating layer 75 are provided on the protective film 72, in order. For example, the insulating film 73 and the insulating layer 75 contain silicon oxide, and the insulating film 74 contains silicon nitride. The insulating films 73 and 74 cover the transistor Tr. Insulating layers 76, 77, and 78 are provided on the insulating film 74 and the insulating layer 75, in order. For example, the insulating layers 76 and 78 contain silicon nitride, and the insulating layer 77 contains silicon oxide.

[0063] Thereafter, as shown in FIG. 5, the insulating layer 40, and a sacrifice layer 81 are alternately stacked on the semiconductor substrate 10 (P-well region 10c) along Z-direction to form a stacked body 15a, using, for example, CVD (Chemical Vapor Deposition) method. The stacked body 15a covers the semiconductor substrate 10 and the insulating layer 78. The insulating layer 40 is formed of, for example, silicon oxide. The sacrifice layer 81 is formed of a material that can provide an etching selectivity ratio for the insulating layers 40. For example, the sacrifice layer 81 is formed of silicon nitride. In the example shown in FIG. 5, the stacked body 15a has a total of six insulating layers 40, and a total of six sacrifice layers 81. However, the number of these layers is not limited to this example.

[0064] Thereafter, as shown in FIG. 6, the stacked body 15a formed on the semiconductor substrate 10 is processed into a stepped shape. For example, in the case of the example shown in FIG. 3, the stepped portion of the stacked body 15a corresponds to the stepped portion of the stacked body 15 with the steps 41s4 to 41s7. Such a stepped portion is formed

using, for example, a photolithography technique that controls the etching amount of the stacked body **15a** by repeating a horizontal etching (Y-direction) of the resist on the stacked body **15a**, and a downward etching (minus Z-direction) of the stacked body **15a**. The etchings remove the stacked body **15a** formed on the insulating layer **78**, and make a stepped portion in the stacked body **15a** formed on the semiconductor substrate **10**. A step **81s** is formed for each sacrifice layer **81**.

[0065] In FIG. 6, a stacked body **82** is a portion that remains after the stacked body **15a** on the semiconductor substrate **10** is processed into a stepped shape.

[0066] Thereafter, as shown in FIG. 7, an insulating layer **83** is formed by depositing silicon oxide on the semiconductor substrate **10** by, for example, a CVD method. The insulating layer **83** covers the stacked body **15a** and the stacked body **82**. The upper surface of the insulating layer **83** is then planarized by CMP (Chemical Mechanical Polishing) method, using, for example, the insulating layer **78** and the uppermost sacrifice layer **81** as stoppers.

[0067] Thereafter, as shown in FIG. 8, a plurality of holes **84** is formed in the stacked body **15a** by, for example, RIE (Reactive Ion Etching). The holes **84** extend in Z-direction from the step **81s** of the uppermost sacrifice layer **81** (see FIG. 6), and reach the semiconductor substrate **10** through the stacked body **15a**. For example, in the case of the example shown in FIG. 3, the step **81s** of the uppermost sacrifice layer **81** corresponds in position to the step **41s4**. For example, the bottom surface of the holes **84** is in the P-well region **10c** of the semiconductor substrate **10**. For example, the holes **84** are circular in shape as viewed from Z-direction. For example, the width **W2** of the holes **84** in an X-Y cross section becomes smaller toward the lower layers of the stacked body **15a**, and is the smallest at the bottom surface of the holes **84**.

[0068] Thereafter, as shown in FIG. 9, an insulating film **85** is formed on the stacked body **15a** and the insulating layers **78** and **83**, using, for example, a CVD method. The insulating film **85** is formed also inside the holes **84**. The insulating film **85** is formed using, for example, silicon oxide.

[0069] Thereafter, as shown in FIG. 10, the upper surface of the insulating film **85** in the holes **84** is planarized by, for example, CMP method. The planarization process removes the insulating film **85** on the stacked body **15a** and on the insulating layers **78** and **83**, leaving the insulating film **85** inside the holes **84**. The upper surface **85a** of the insulating film **85** in the holes **84** is substantially at the same level as, for example, the upper surface **78a** of the insulating layer **78**. The lower surface **85b** of the insulating film **85** in the holes **84** is in contact with the semiconductor substrate **10** (P-well region **10c**).

[0070] Thereafter, as shown in FIG. 11, the insulating layer **40** and the sacrifice layer **81** are alternately stacked in Z-direction on the stacked body **15a** and the insulating layers **78** and **83** to form a stacked body **15b**, using, for example, a CVD method. In the example shown in FIG. 11, the stacked body **15b** has a total of six insulating layers **40**, and a total of six sacrifice layers **81**. However, the number of these layers is not limited to this example.

[0071] The following describes a manufacturing process of the memory cell region Rmc and the contact region Rc with reference to FIG. 12 to FIG. 17.

[0072] After the process shown in FIG. 11, the stacked body **15b** is processed into a stepped shape, as shown in FIG. 12. The stepped portion of the stacked body **15b** is formed in Y-direction, continuously from the stepped portion of the stacked body **15a**. For example, in the case of the example shown in FIG. 3, the stepped portion of the stacked body **15b** corresponds to the stepped portion of the stacked body **15** with the steps **41s1** to **41s3**. Such a stepped portion is formed using, for example, a photolithography technique that controls the etching amount of the stacked body **15b** by repeating a horizontal etching (Y-direction) of the resist on the stacked body **15b**, and a downward etching (minus Z-direction) of the stacked body **15b**. The etchings make a stepped portion in the stacked body **15b**, and the step **81s** is formed for each sacrifice layer **81**.

[0073] Thereafter, as shown in FIG. 13, silicon oxide is deposited on the insulating layer **83** to form an insulating layer **45**, using, for example, a CVD method. The insulating layer **83** is a portion of the insulating layer **45**. The insulating layer **45** covers the stacked body **15a**, and the stepped portion of the stacked body **15b**. Silicon oxide is then deposited on the stacked body **15b** and the insulating layer **45** to form the insulating layers **42** and **43**, in order.

[0074] Thereafter, as shown in FIG. 14, a plurality of memory holes MH is formed in the stacked bodies **15a** and **15b**, and a plurality of holes **86** is formed in the stacked body **15a**.

[0075] The memory holes MH are formed by, for example, RIE. The memory holes MH extend in Z-direction, and reach the semiconductor substrate **10** through the insulating layers **42** and **43**, and the stacked bodies **15a** and **15b**. For example, the bottom surface of the memory holes MH is in the P-well region **10c** of the semiconductor substrate **10**. For example, the memory holes MH are circular in shape as viewed from Z-direction.

[0076] The holes **86** extend in Z-direction, and reach the semiconductor substrate **10** through the insulating layers **42**, **43**, and **45**, and the stacked body **15a**. The holes **86**, formed by, for example, a photolithography technique and etching, extend in Z-direction through the insulating layers **42**, **43**, and **45**, and reach the semiconductor substrate **10** through the stacked body **15a** by extending into the insulating film **85** from directly above the insulating film **85**. In the example shown in FIG. 3, the holes **86** penetrate through the step **41s4**. This forms the insulating film **51**. For example, the bottom surface of the holes **86** is in the P-well region **10c** of the semiconductor substrate **10**. For example, the holes **86** are circular in shape as viewed from Z-direction.

[0077] After the formation of the memory holes MH, the connecting member **10d** is formed by, for example, epitaxial growth of silicon from inside of the semiconductor substrate **10** into the stacked body **15a**.

[0078] Thereafter, as shown in FIG. 15, silicon oxide is deposited on the inner surface of the memory holes MH to form the block insulating film **23** (see FIG. 2), using, for example, a CVD method. Silicon nitride is deposited to form the charge storage film **22** (see FIG. 2), and silicon oxide is deposited to form the tunnel insulating film **21** (see FIG. 2). Thereafter, silicon is deposited to form the cover layer **20b**. This is followed by RIE, which removes the cover layer **20b**, the tunnel insulating film **21**, the charge storage film **22**, and the block insulating film **23**, and exposes the connecting member **10d**. This forms the memory film **24**.

[0079] Silicon oxide, silicon nitride, and silicon oxide are deposited in order on the inner surface of the holes 86 to form a multilayer film, and silicon is deposited to form the cover layer 20b1. This is followed by RIE, which removes the cover layer 20b1 and the multilayer film, and exposes the insulating film 51. This forms the memory film 24A.

[0080] Thereafter, silicon is deposited in the memory holes MH to form the body 20a, and silicon oxide is deposited to form the core portion 60. This forms the channel 20. The columnar members 55 having the core portion 60, the channel 20, and the memory film 24 are formed after this process. The body 20a of the channel 20 is in contact with the connecting member 10d formed in the semiconductor substrate 10.

[0081] Silicon is deposited in the holes 86 to form the body 20a1, and silicon oxide is deposited to form the core portion 60A. This forms the channel 20A. The columnar members 50 having the core portion 60A, the channel 20A, and the memory film 24A are formed after this process. The bottom portion 50a of the columnar members 50 is covered by the insulating film 51.

[0082] Thereafter, the upper part of the core portion 60 in the memory holes MH, and the core portion 60A in the holes 86 are removed by being etched back, and impurity-doped silicon is embedded to form the plug portion 61 and the plug portion 61A.

[0083] Thereafter, as shown in FIG. 16, the slits ST (see FIG. 3) are formed that extend through the stacked bodies 15a and 15b in Y-direction, using, for example, RIE. The slits ST penetrate through the insulating layers 42 and 43, and the stacked bodies 15a and 15b. In this way, the slits ST divide the stacked bodies 15a and 15b into a plurality of stacked bodies that extends in Y-direction.

[0084] This is followed by wet etching via the slits ST. This removes the sacrifice layer 81 (see FIG. 15). When the sacrifice layer 81 is formed using silicon nitride, phosphoric acid is used as an etchant for wet etching, and etching is performed with hot phosphoric acid. The removal of the sacrifice layer 81 via the slits ST forms cavities 87. The columnar members 50 in the stacked body 15a reduce warping of the stacked bodies 15a and 15b due to the cavities 87.

[0085] Thereafter, as shown in FIG. 17, a conductive material such as tungsten is deposited to fill the cavities 87. This forms the electrode layers 41 having the drain-side select gate SGD, the source-side select gate SGS, and the word lines WL. In this manner, the sacrifice layers 81 are replaced by the electrode layers 41, and the stacked body 15 is formed between the slits ST. The stacked body 15 has the central portion 15A with the columnar members 55, and the end portion 15B with the columnar members 50. The electrode layers 41 formed in the end portion 15B have a stepped shape, with the step 41s formed for each electrode layer 41.

[0086] Thereafter, silicon oxide is deposited on the inner surface of the slits ST to form an insulating film, and a metal such as tungsten is deposited to form the interconnect portion 18 (see FIG. 3). After forming the insulating layer 44 on the insulating layer 43, contact holes are formed through the insulating layer 44, and a metallic material such as tungsten is embedded in the contact holes to form the contact portions Cb. Thereafter, the bit lines BL to be connected to the contact portions Cb are formed.

[0087] Contact holes through the insulating layers 44, 43, 42, and 45 are formed, and a metallic material such as tungsten is embedded in the contact holes to form the contacts 30 (see FIG. 3). The contacts 30 are formed on the steps 41s.

[0088] This completes the semiconductor memory device 1 of the embodiment.

[0089] In the semiconductor memory device 1 of the embodiment, the insulating film 51 is provided that covers the bottom portion of the columnar members 50 of the stacked body 15. By the provision of the insulating film 51, the bottom surface of the columnar members 50 does not contact the semiconductor substrate 10, and the columnar members 50 can be electrically insulated from the semiconductor substrate 10. This suppresses the passage of a leak current from the contact 30 to the semiconductor substrate 10 via the columnar member (channel 20A) even when, for example, the columnar member 50 and the contact 30 contact, and conduct electricity as a result of a misalignment occurring in the contacts 30. Accordingly, the passage of a leak current to the columnar members 55 on the semiconductor substrate 10 can be suppressed. The semiconductor memory device 1 thus becomes less likely to fail in performing operations, for example, in memory operations such as a write operation.

[0090] A reliable semiconductor memory device can be achieved with the embodiment described above.

[0091] While certain embodiments have been described, these embodiments have been presented by way of example only, and are not intended to limit the scope of the inventions. Indeed, the novel embodiments described herein may be embodied in a variety of other forms; furthermore, various omissions, substitutions and changes in the form of the embodiments described herein may be made without departing from the spirit of the inventions. The accompanying claims and their equivalents are intended to cover such forms or modifications as would fall within the scope and spirit of the invention.

1. A semiconductor memory device comprising:
 - a substrate;
 - a stacked body provided on the substrate and including a plurality of electrode layers separately stacked each other;
 - a columnar member provided in the stacked body and including a first semiconductor portion extending in a stacked direction of the plurality of electrode layers; and
 - an insulating film covering a bottom portion of the columnar member;
 - a portion of the insulating film being located between one of the plurality of electrode layers of the stacked body and the columnar member.
2. The device according to claim 1, wherein the insulating film contains silicon oxide.
3. The device according to claim 1, wherein the insulating film has a shape of a bottomed cylinder.
4. The device according to claim 1, wherein the insulating film has a thickness in a direction along an upper surface of the substrate, the thickness becoming smaller toward the lower layers of the stacked body.
5. The device according to claim 1, wherein the columnar member includes a multilayer film provided between the first semiconductor portion and the stacked body, and

the portion of the insulating film is located between the one of the plurality of electrode layers of the stacked body and the multilayer film.

6. The device according to claim 1, further comprising a first insulating layer covering a portion of the stacked body, wherein the stacked body includes a stepped end portion with a step provided for each of the electrode layers,

the first insulating layer covers the end portion of the stacked body,

the columnar member extends in the end portion and in the first insulating layer in the stacked direction, and at least one portion of the insulating film is located in the end portion.

7. The device according to claim 6, wherein the portion of the insulating film is located in the first insulating layer.

8. The device according to claim 1, further comprising: a second semiconductor portion provided in the stacked body and extending in the stacked direction;

a charge storage film provided between the second semiconductor portion and the stacked body; and a first interconnection provided on the stacked body and connected to the second semiconductor portion.

9. The device according to claim 1, further comprising: a peripheral circuit provided around the stacked body and including a switching element, and a second insulating layer provided on the switching element,

wherein an upper surface of the insulating film is located on substantially a same plane as an upper surface of the second insulating layer.

10. A semiconductor memory device comprising:

a substrate;

a stacked body provided on the substrate and including a plurality of electrode layers separately stacked each other;

a first semiconductor portion provided in the stacked body and extending in a stacked direction of the plurality of electrode layers;

a first charge storage film provided between the first semiconductor portion and the stacked body;

a second semiconductor portion provided in the stacked body, extending in the stacked direction, and containing a same material contained in the first semiconductor portion; and

an insulating film covering a bottom surface and a side surface of the second semiconductor portion;

a portion of the insulating film being located between one of the plurality of electrode layers of the stacked body and the second semiconductor portion.

11. The device according to claim 10, wherein the insulating film contains silicon oxide.

12. The device according to claim 10, wherein the insulating film has a shape of a bottomed cylinder.

13. The device according to claim 10, wherein a portion of the insulating film is located in the substrate.

14. The device according to claim 10, wherein the insulating film has a thickness in a direction along an upper surface of the substrate, the thickness becoming smaller toward the lower layers of the stacked body.

15. The device according to claim 10, further comprising a second charge storage film provided between the second semiconductor portion and the stacked body and containing a same material contained in the first charge storage film.

16. The device according to claim 15, wherein the portion of the insulating film is located between the one of the plurality of electrode layers of the stacked body and the second charge storage film.

17. The device according to claim 16, wherein the insulating film between the stacked body and the second charge storage film has a thickness in a direction along an upper surface of the substrate, the thickness becoming smaller toward the lower layers of the stacked body.

18. The device according to claim 15, further comprising a first interconnection provided on the stacked body and connected to the first semiconductor portion,

wherein the first semiconductor portion includes a first body, and a first cover layer provided between the first body and the first charge storage film,

the second semiconductor portion includes a second body, and a second cover layer provided between the second body and the second charge storage film, and

the insulating film covers a bottom surface of the second body.

19. The device according to claim 10, further comprising an insulating layer covering a portion of the stacked body, wherein the stacked body includes a stepped end portion with a step provided for each of the electrode layers, the insulating layer covers the end portion of the stacked body,

the second semiconductor portion extends in the end portion and in the insulating layer in the stacked direction, and

at least one portion of the insulating film is located in the end portion.

20. The device according to claim 19, wherein the portion of the insulating film is located in the insulating layer.

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